# GaN HEMT Device Model Development for Implementation of Different Circuit Designs

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#### Abstract

GaN HEMT devices (with different dimensions) have been investigated using 16- and 22-element smallsignal equivalent circuit Model. The percentage error is estimated to show the difference in extracted parameters using 16- and 22-element small-signal equivalent circuit model which assist in choosing the accurate small-signal model for large gate periphery GaN HEMTs. For device's low power operation linear models are sufficient. In order to achieve higher certainty for high power applications, the nonlinear behaviour of the device must be considered. While generating the large-signal device model, the nonlinear capacitances  $C_{gs}$  and  $C_{gd}$ , as well as the current source  $I_{ds}$  are primarily considered to capture the non-linear behavior of the device. The capacitances,  $C_{gs}$  and  $C_{gd}$ , are dependent on applied bias i. e.  $V_{gs}$  and  $V_{ds}$ . The Angelov model for  $I_{ds}$  is used to generate the non-linear model parameters which uses the multi-bias small-signal equivalent circuit parameters.

**Keywords:** HEMT, I-V Characteristc, S-Parameter, 16- and 22-Element Equivalent Circuit Model, Large-Signal Model.

### **INTRODUCTION**

Gallium nitride-based HEMTs (high-electron mobility transistor) provides higher cut-off frequency and higher breakdown voltage and shows outstanding power and frequency performance over the past decade [1] [2]. GaN HEMTs are now the most promising devices for RF switches, low noise amplifiers and power amplifiers, which are essential components of transceiver systems. The need for an accurate device model becomes paramount for the design and analysis of any active circuit. Small-signal equivalent circuit models are adequate for low power operation devices. The nonlinear behaviour of the device must be considered in order to obtain high accuracy for high power applications. GaN device modeling has been the subject of numerous reported works. There have been claimed to be several ways to simulate GaN HEMTs, each with advantages and disadvantages [3] [4] [5] [6] [7]. Several large-signal HEMT models (empirical equation based), including the ASM HEMT model [8], Curtice model [9] and Angelov (Chalmers) model [10], have previously been created and integrated with several commercial computer-aided design (CAD) programs. Different formulas are used by these models, based on the I-V characteristics between the subthreshold and saturation area. to fit the electrical behavior of the device.

In this work, the 16- and 22-element small signal model were used for parameters extraction. GaN HEMT devices

with Different dimensions have been investigated using these techniques. The device's Stability Factor, K-factor, Maximum Gain and Delta Factor were simulated. The 16- and 22-element small signal equivalent circuit models are compared and the percentage error were estimated to depict the preciseness of 16- and 22-element small signal model to be chosen for large gate perphery devices.

The small model should be accurate, easy to apply in commercial simulators and relatively quick to extract. In this work, the multi-bias small-signal equivalent circuit parameters are extracted which is beneficial in generating the non-linear model of the device.

# **EXTRACTION METHODOLOGY**

Small-signal model of the microwave transistor has been the subject of much debate and is still debated [20-22], due to the interests and challenges this area of research.

The small-signal models often act as the basis of largesignal and noise modelling which provides the main reason for such a great interest. The small-signal equivalent circuits used for the parameter extraction are shown in figure 2 (a) and (b). Figure 2 (a) shows the 16element circuit consisting of 8 intrinsic and 8 extrinsic parameters and figure 2 (b) shows the 22-element circuit consisting of 10 intrinsic and 12 extrinsic elements. The intrinsic elements are surrounded by the dash lines in figure 2(a) and (b). These models consider the the parasitic resistances (R<sub>s</sub>, R<sub>g</sub> and R<sub>d</sub>); contact inductances  $(L_g, L_s \text{ and } L_d)$ ; the gate and drain pad capacitances  $(C_{pg})$ and  $C_{pd}$ ). The  $C_{gd}$ ,  $C_{gs}$  and  $C_{ds}$  are the intrinsic capacitances between different contacts (such as gatedrain, gate-source and drain-source). gd and gm represents the output and intrinsic transconductances. The channel resistance associated are  $R_i$  and  $R_{gd}.$  The  $\tau$  is the time delay i.e. the change of gate voltage w. r. t. drain current. The parasitic pad capacitances were differentiated as 6 different capacitances in 22-element model: Cpdi, Cpgi,  $C_{\text{gdi}},\ C_{\text{pda}},\ C_{\text{pga}}$  and  $C_{\text{gda}}.\ G_{\text{gsf}}$  and  $G_{\text{gdf}}$  models the conduction current through the gate-source and gatedrain terminals. The conventional approach has been considered for extraction of parameters and has been depicted as a flow chart in figure 3. First, the experimental [19] S-parameter at  $V_{gs}\!\!=\!\!-5$  V and  $V_{ds}\!\!=\!\!0$  V (cold pinch off condition) is used to estimate the pad capacitances. When determining the parasitic inductances and resistances,  $V_{gs}$  and  $\bar{V}_{ds}$  in a cold HEMT measurement, i.e., 0 V. The curve fitting method is then applied to quantify the resistances and inductances. Additionally, the parasitic capacitances and resistance under the gate are considered [12], the extrinsic parameters' fidelity is increased, and this is crucial for the intrinsic parameters to be accurate.

The measured s-parameters are transformed into Z- and Y-parameters at  $V_{gs}$ =-3 V and  $V_{ds}$  = 10 V, followed by the extrinsic parameters de-embedding, to obtain the intrinsic parameters. These extrinsic and intrinsic parameters are the initial values for the circuit simulation.



(b) Fig. 2. (a) 16-Element Small-Signal Equivalent Circuit Model and (b) 22-Element Small-Signal Equivalent Circuit Model.

Subsequent to the extraction small-signal equivalent circuit is designed in ADS software using these parameter initial values followed by the optimization and tuning the parameters to get good congruency between the measured and simulated s-parameters.



Fig. 3. Flow chart representation of parameter extraction technque.



Fig. 4. Comparison of (a) Maximum Gain and Stability Factor, (b) K-Factor and (c) Delta Factor between the measured, 16- and 22-element small-signal model of GaN HEMT.

### **RESULTS AND DISCUSSION**

Following the extraction procedure, explained by the flow chart in figure 3, the intrinsic and extrinsic

parameters were extracted using 16- and 22-element model using the measured s-parameters. The circuit was designed in ADS and S-parameter were simulated (frequency range 500 MHz to 26 GHz). To get a good congruency between the measured and simulated results, the optimization and tuning tools in ADS were used to tune the parameters [19] for both the models. The GaN HEMT devices, having different dimensions, were investigated. After optimization, the Stability Factor, Kfactor, Maximum Gain and Delta Factor were simulated using both the models. The Stability Factor, K-factor, Delta Factor and Maximum Gain are represented (in terms of S-parameters) as follows [23]:

Stability Factor =  $1 + |S_{11}|^2 - |S_{22}|^2 - |S_{11}*S_{22} - S_{12}*S_{21}|^2$ .....(1)

$$K\text{-Factor} = \{1 - |S_{11}|^2 - |S_{22}|^2 + |\Delta|^2\} / \{2^*|S_{12}^*S_{21}|\}$$

 $Delta \ Factor = \Delta = S_{11} * S_{22} - S_{12} * S_{21}$ ......(3)

Max. Gain =
$$(K \cdot \sqrt{(K^2 - 1)})^*(S_{21}/S_{12})$$

The results obtained for Stability Factor, K-factor, Maximum Gain and Delta Factor for 16- and 22- element models were compared with the measured data which are depicted in figure 4 (a-c). The % error, depicted in figure 5 (a-d) were calculated between the simulated 16and 22-element model with measured [19] Stability Factor, K-factor, Maximum Gain and Delta Factor for GaN HEMTs. From figure 5, it can be observed that, as the source to drain distance is increased, the percentage error is reducing for the 22-element model. In case of stability factor the reduction is as following:13.47%-8.11% with difference of 5.36% for  $L_{sd}=2.5 \mu m$ , 13.05%-7.40% with difference of 5.65% for Lsd=3.0 µm and 10.42%-4.74% with difference of 5.68% for L<sub>sd</sub>= $4.0 \mu m$ . Analogous effect can be observed for the increased number of fingers of the device. Thus can be concluded that the 22-element model gives more accurate smallsignal equivalent circuit model for large gate periphery devices [19].

The intrinsic parameters have been extracted for different  $V_{gs}$  and  $V_{ds}$  as these parameters are bias dependent. The intrinsic parameters were optimized (extrinsic element values were constant). The RF characteristics (fT, fMax., voltage gain, current gain, power gain) of the GaN HEMT are the functions of device intrinsic parameters. The intrinsic parameters of the device are dependent on the gate and drain bias. Hence, the gate and drain bias will affect the RF characteristics (fT, fMax., voltage gain, current gain) of the GaN HEMT. To show the bias dependency of the intrinsic parameters, the extraction were carried out for different  $V_{gs}$  and  $V_{ds}$ . Fig. 6 (a-f) represents the intrinsic parameters versus gate bias for different drain bias.



The depletion layer behind the gate controls the capacitance (Cgs) between the gate metal and channel charge in 2DEG. When V<sub>gs</sub> rises from the pinchoff region, C<sub>gs</sub> rises as well. Beyond a certain voltage, the drain current saturates as  $V_{\text{gs}}$  rises, and the depletion area stops changing.  $C_{gs}\xspace$  and  $V_{gs}\xspace$  become constant at that voltage. The drain voltage creates a lateral electric field that accelerates the channel's carriers. As a result, the depletion layer depth is decreased, which leads to a modest increase in  $C_{gs}$  with  $V_{ds}$ . The extended depletion region in the gate-drain area is the cause of C<sub>gd</sub>. This depletion area widens as the drain voltage rises. As a result, a slight rise in  $C_{gd}$  with rising  $V_{ds}$  can be seen. A collapse follows a strong increase in the Gm-Vgs characteristic that occurs above pinch-off voltage which can be observed in figure 6(c).



Fig. 5. The percentage Error Between The 16- And 22-Element Model Simulated with Measured (a) Maximum Gain, (b) Stability Factor, (c) K-Factor and (d) Delta Factor.



Due to the abrupt increase in current with  $V_{ds}$ ,  $G_d$  grows with  $V_{gs}$  at low  $V_{ds}$ . However, in the saturation zone,  $G_d$ is minimal. With  $V_{gs}$  and  $V_{ds}$ ,  $R_i$  and  $R_{gd}$  rise. The transit time for the electrons grows longer as the depletion zone spreads in the gate-drain region. As a result, rises with  $V_{gs}$  and Vds.

After the multibias linear model extraction, the nonlinear model of the device can be developed. While generating the large-signal model, the non-linear



Fig. 6. Bias dependent intrinsic parameters for GaN HEMT with 0.4  $\mu$ m gate length and source to drain length 2.5  $\mu$ m.

behavior of the device must be captured. Hence, the nonlinear capacitances  $C_{gs}$  and  $C_{gd}$ , as well as the current source  $I_{ds}$ , are primarily considered. The current source  $(I_{ds})$  demonstrates the electrical performance of HEMT, which is controlled by Gate voltage and drain voltage. The I-V characteristic of the device can be accurately modeled using this non-linear current source.

## CONCLUSION

The findings from the 22-element model demonstrate strong correlation and fewer percentage mismatch with the measured data. The devices with large gate periphery show high accuracy. Hence, the 22-element model gives more accurate small-signal equivalent circuit model for large gate periphery devices. The large-signal model for GaN HEMT device can be generated for further circuit design implimentations with precision to measured results using the multi-bias small-signal equivalent circuit parameters.

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